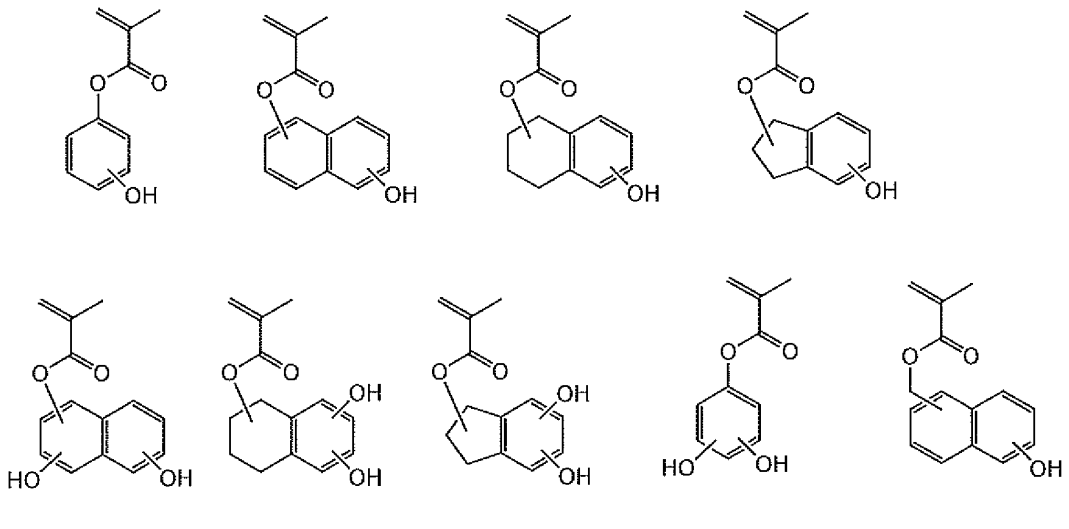
CLAIMS

[1] A fine pattern-forming composition for miniaturizing a resist pattern by fattening in a process of forming a negative resist pattern from a chemically amplified resist composition,

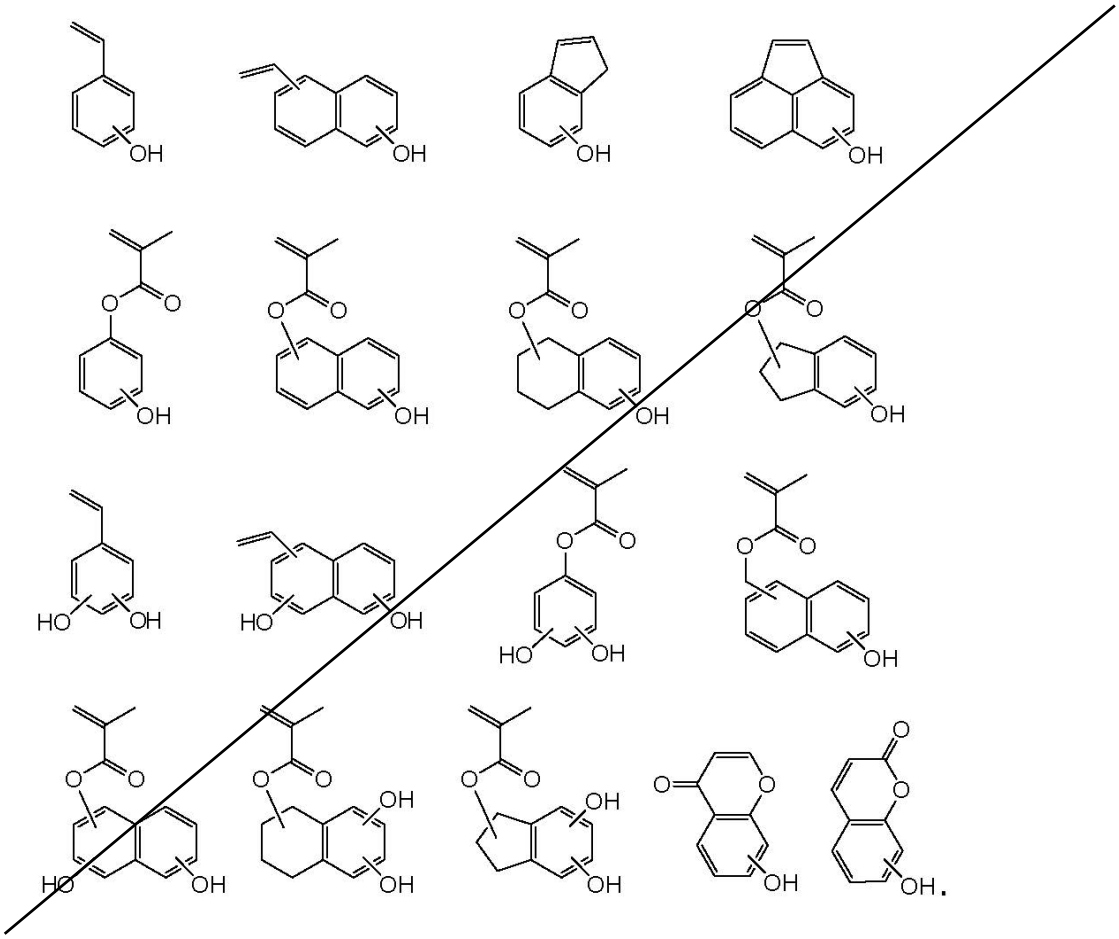
comprising

a polymer containing a repeating unit having a hydroxylaryl group, and an organic solvent not dissolving said negative resist pattern wherein said polymer contains the repeating unit having a hydroxyaryl group in an amount of 60 mol% or more based on the number of moles of all the repeating units, and further wherein said repeating unit is derived from at least one monomer selected from the group consisting of



~~[2] The fine pattern-forming composition according to claim 1, wherein said hydroxyaryl group is selected from the group consisting of monohydroxyphenyl, dihydroxyphenyl, mono-hydroxynaphthyl and dihydroxynaphthyl.~~

~~[3] The fine pattern-forming composition according to claim 1, wherein said repeating unit is derived from at least one monomer selected from the group consisting of~~



~~[4] The fine pattern-forming composition according to any of claims 1 to 3, wherein said polymer contains the repeating unit having a hydroxyaryl group in an amount of 60 mol% or more based on the number of moles of all the repeating units.~~

[2~~5~~] The fine pattern-forming composition according to claim 1~~any of claims 1 to 4~~, wherein said organic solvent contains 2-heptanone or butyl acetate.

[3~~6~~] The fine pattern-forming composition according to claim 2~~5~~, which contains 2-heptanone or butyl acetate in an amount of 80 wt% or more.

[4~~7~~] A method for forming a fine negative resist pattern, comprising the steps of

(1) coating a semiconductor substrate with a chemically amplified resist composition, to form a photoresist layer;

(2) exposing to light said semiconductor substrate coated with said photoresist layer;

(3) developing said photoresist layer with an organic solvent developer after said exposing step, to form a photoresist pattern;

(4) coating said photoresist pattern with the fine pattern-forming composition according to claim 1~~any of claims 1 to 6~~;

(5) heating the coated photoresist pattern, and

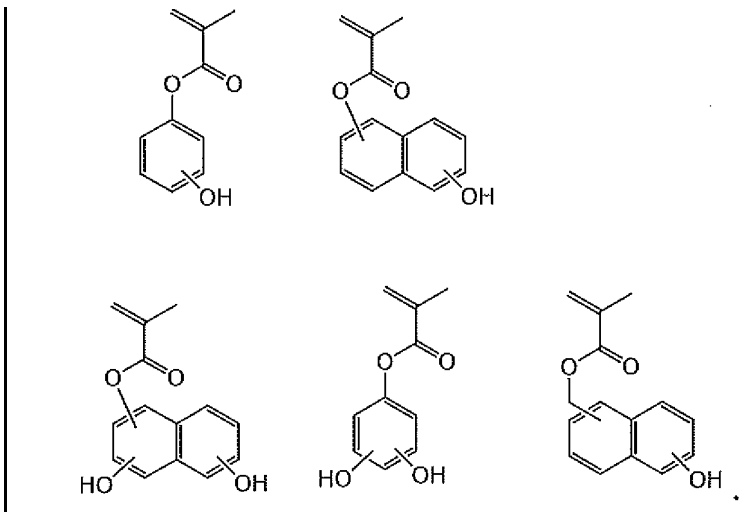
(6) washing to remove excess of the fine pattern-forming composition.

[5~~8~~] The method according to claim 4~~7~~, wherein said steps (1) and (4) are carried out by means of the same coating apparatus.

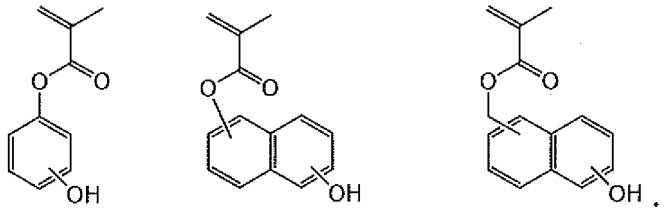
[6~~9~~] The method according to claim 4~~7 or 8~~, wherein said step (6) is carried out by use of 2-heptanone or butyl acetate.

[7] The method according to claim 4, wherein said step (6) is carried out by use of 2-heptanone or butyl acetate.

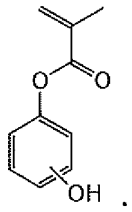
[8] The fine pattern-forming composition according to claim 1, wherein said repeating unit is derived from at least one monomer selected from the group consisting of



[9] The fine pattern-forming composition according to claim 1, wherein said repeating unit is derived from at least one monomer selected from the group consisting of



[10] The fine pattern-forming composition according to claim 1, wherein said repeating unit is derived from is derived from at least one monomer selected from



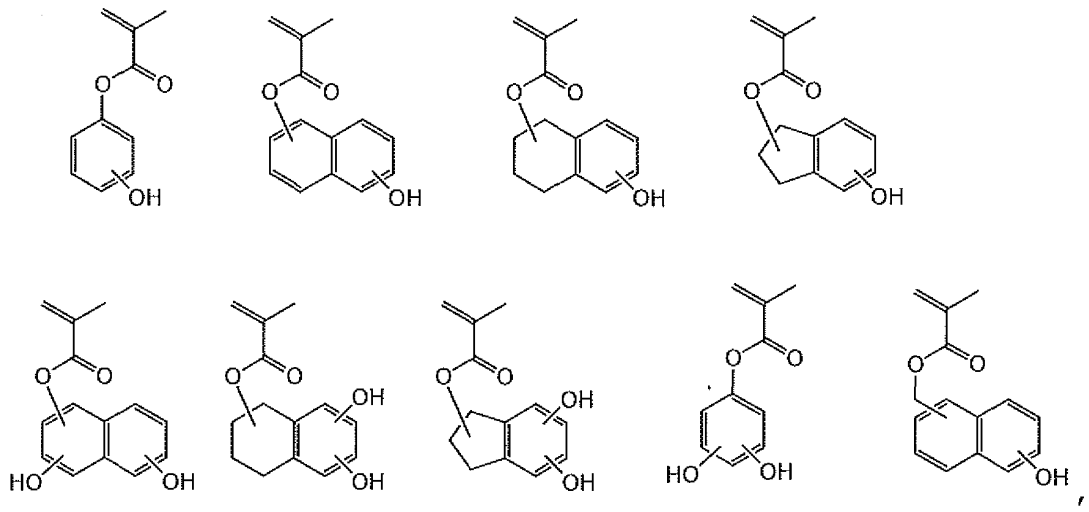
[11] The fine pattern-forming composition according to claim 1, wherein the composition does not contain a compound with a free carboxyl group.

[12] A fine pattern-forming composition for miniaturizing a resist pattern by fattening in a process of forming a negative resist pattern from a chemically amplified resist composition,

consisting essentially of

a polymer containing a repeating unit having a hydroxylaryl group, an organic solvent not dissolving said negative resist pattern wherein said polymer contains the repeating unit having a hydroxyaryl group in an amount of 60 mol% or more based on the number of moles of all the repeating units,

and further wherein said repeating unit is derived from at least one monomer selected from the group consisting of



and optional additives selected from the group consisting of surfactants, germicides, antibacterial agents, antiseptic agents and anti-mold agents.